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1. **Imaging of retina cellular and subcellular structures using ptychographic hard X-ray tomography**
Valérie Panneels, Ana Diaz, Cornelia Imsand, Manuel Guizar-Sicairos, Elisabeth Müller, Anne Greet Bitterman, Takashi Ishikawa, Andreas Menzel, Andres Kaech, Mirko Holler, Christian Grimm, Gebhard Schertler
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2. **Correlation between Oxygen Vacancies and Oxygen Evolution Reaction Activity for a Model Electrode: $\text{PrBaCo}_2\text{O}_{5+\delta}$**
Elena Marelli, Jaume Gazquez, Emiliya Poghosyan, Elisabeth Müller, Dariusz J. Gawryluk, Ekaterina Pomjakushina, Denis Sheptyakov, Cinthia Piamonteze, Dino Aegerter, Thomas J. Schmidt, Marisa Medarde, and Emiliana Fabbri
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3. **Pt catalytic effects on the corrosion and hydrogen chemisorption properties of Zircaloy-2**
Sriharitha Rowthu, Pascal V. Grundler, Elisabeth Müller, Stefan Ritter
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4. **Design guidelines for an electron diffractometer for structural chemistry and structural biology**
Jonas Heidler, Radosav Pantelic, Julian T. C. Wennmacher, Christian Zaubitzer, Ariane Fecteau-Lefebvre, Kenneth N. Goldie, Elisabeth Müller, Julian J. Holstein, Eric van Genderen, Sacha De Carlo and Tim Gruene
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5. **Three-dimensional imaging of integrated circuits with macro- to nanoscale zoom**
Mirko Holler, Michal Odstrcil, Manuel Guizar-Sicairos, Maxime Lebugle, Elisabeth Müller, Simone Finizio, Gemma Tinti, Christian David, Joshua Zusman, Walter Unglaub, Oliver Bunk, Jörg Raabe , A. F. J. Levi and Gabriel Aepli
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6. **Ferroelectric Self-Poling in GeTe Films and Crystals**
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7. **Multiferroic phase diagram of E-type RMnO_3 films studied by neutron and x-ray diffraction**
Saumya Mukherjee, Kenta Shimamoto, Yoav William Windsor, Mahesh Ramakrishnan, Sergii Parchenko, Urs Staub, Laurent Chapon, Bachir Ouladdiaf, Marisa Medarde, Tian Shang, Elisabeth A. Müller, Michel Kenzelmann, Thomas Lippert, Christof W. Schneider, and Christof

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9. **Combustion generated nanomaterials: online characterization via an ICP-MS based technique. Part II: resolving power for heterogeneous matrices**
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13. **Resonant Ptychographic Tomography Facilitates Three-Dimensional Quantitative Colocalization of Catalyst Components and Chemical Elements**
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